



# **STIC Search Report**

**EIC 1700**

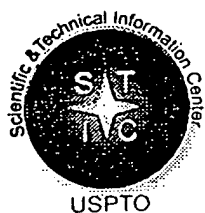
**STIC Database Tracking Number: 144875**

**TO: Hoa V Le**  
**Location: REM 9D61**  
**Art Unit : 1752 9879**  
**February 22, 2005**

**Case Serial Number: 10/622493**

**From: Usha Shrestha**  
**Location: EIC 1700**  
**REMSSEN 4B28**  
**Phone: 571/272-3519**  
**usha.shrestha@uspto.gov**

## **Search Notes**



# STIC Search Results Feedback Form

**EIC17000**

Questions about the scope or the results of the search? Contact *the EIC searcher* or contact:

Kathleen Fuller, EIC 1700 Team Leader  
571/272-2505 REMSEN 4B28

## Voluntary Results Feedback Form

- I am an examiner in Workgroup:  Example: 1713  
➤ Relevant prior art **found**, search results used as follows:

- ☐ 102 rejection
- ☐ 103 rejection
- ☐ Cited as being of interest.
- ☐ Helped examiner better understand the invention.
- ☐ Helped examiner better understand the state of the art in their technology.

Types of relevant prior art found:

- ☐ Foreign Patent(s)
- ☐ Non-Patent Literature  
(journal articles, conference proceedings, new product announcements etc.)

➤ Relevant prior art **not found**:

- ☐ Results verified the lack of relevant prior art (helped determine patentability).
- ☐ Results were not useful in determining patentability or understanding the invention.

Comments:

Drop off or send completed forms to EIC1700 REMSEN 4B28

Access DB# 144875**SEARCH REQUEST FORM**

Scientific and Technical Information Center

Requester's Full Name: HOA VAN LE Examiner #: 60626 Date: 02/10/05  
Art Unit: 1752 Phone Number 301(71)272-1332 Serial Number: 10/622,493  
Mail Box and Bldg/Room Location: 40121 Results Format Preferred (circle): PAPER DISK E-MAIL

**If more than one search is submitted, please prioritize searches in order of need.**

\*\*\*\*\*

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and contribute to the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

FEB 10

Title of Invention: \_\_\_\_\_ Pat. &amp; T.M. Office

Inventors (please provide full names): \_\_\_\_\_ *please see the attachment*

Earliest Priority Filing Date: \_\_\_\_\_

\*For Sequence Searches Only\* Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

*Please search for the compounds of the general formula I. Please see compounds Y(1-22) on pages 31-33, especially compound Y-1 as specifically elected.*

*The compound is in an aqueous alkaline solution (pH greater than 7).*

*Thank you.*

\*\*\*\*\*

**STAFF USE ONLY**

	Type of Search	Vendors and cost where applicable
Searcher: <u>isha</u>	NA Sequence (#) _____	STN <u>88735</u>
Searcher Phone #: _____	AA Sequence (#) _____	Dialog _____
Searcher Location: _____	Structure (#) <u>5</u>	Questel/Orbit _____
Date Searcher Picked Up: <u>2/22/05</u>	Bibliographic _____	Dr.Link _____
Date Completed: <u>2/22/05</u>	Litigation _____	Lexis/Nexis _____
Searcher Prep & Review Time: <u>70</u>	Fulltext _____	Sequence Systems _____
Clerical Prep Time: <u>50</u>	Patent Family _____	WWW/Internet _____
Online Time: <u>200</u>	Other _____	Other (specify) _____

10/622,493

Division of Application No. ~~10/187,605~~

Attorney's Docket No. 018995-735

Page 14

**CLAIM SUMMARY DOCUMENT**

1. (Original) A developer for a photopolymerizable presensitized plate for use in making a lithographic printing plate characterized in that it comprises an alkali silicate and a nonionic compound represented by the following general formula (I), it has a molar ratio:  $\text{SiO}_2/\text{M}_2\text{O}$  (wherein M represents an alkali metal or an ammonium group) ranging from 0.75 to 4.0, and a pH value ranging from 11.5 to 12.8:

A-W (I)

wherein A represents a hydrophobic organic group whose logP as determined for A-H is not less than 1.5 and W represents a nonionic hydrophilic organic group whose logP as determined for W-H is less than 1.0.

2. (Original) The developer for a photopolymerizable presensitized plate for use in making a lithographic printing plate of claim 1, wherein the alkali silicate is selected from the group consisting of sodium silicate, potassium silicate, lithium silicate and ammonium silicate.

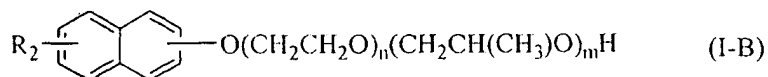
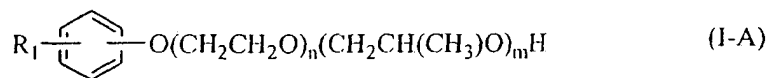
3. (Original) The developer for a photopolymerizable presensitized plate for use in making a lithographic printing plate of claim 1, wherein the molar ratio:  $\text{SiO}_2/\text{M}_2\text{O}$  ranges from 1.0 to 3.0.

4. (Original) The developer for a photopolymerizable presensitized plate for use in making a lithographic printing plate of claim 1, wherein the content of the alkali silicate

ranges from 0.1 to 3% by weight as expressed in terms of the amount of silicon dioxide (SiO<sub>2</sub>).

5. (Original) The developer for a photopolymerizable presensitized plate for use in making a lithographic printing plate of claim 1, wherein the content of the nonionic compound ranges from 0.1 to 15% by weight.

6. (Original) The developer for a photopolymerizable presensitized plate for use in making a lithographic printing plate of claim 1, wherein the nonionic compound is at least one member selected from the group consisting of nonionic aromatic ether type surfactants represented by the following general formula (I-A) and nonionic aromatic ether type surfactants represented by the following general formula (I-B):



wherein R<sub>1</sub> and R<sub>2</sub> each represents H or an alkyl group having 1 to 100 carbon atoms and n and m each represents an integer ranging from 0 to 100, provided that n and m are not simultaneously zero.

7. (Original) The developer for a photopolymerizable presensitized plate for use in making a lithographic printing plate of claim 1, wherein it comprises carbonic acid or a carbonate.

8. (Original) The developer for a photopolymerizable presensitized plate for use in making a lithographic printing plate of claim 1, wherein it comprises an alkaline agent selected from the group consisting of sodium hydroxide, potassium hydroxide, lithium hydroxide, sodium tertiary phosphate, potassium tertiary phosphate, ammonium tertiary phosphate, sodium secondary phosphate, potassium secondary phosphate, ammonium secondary phosphate, sodium carbonate, potassium carbonate, ammonium carbonate, sodium bicarbonate, potassium bicarbonate, ammonium bicarbonate, sodium borate, potassium borate and ammonium borate, potassium citrate, sodium citrate, monomethylamine, dimethylamine, trimethylamine, monoethylamine, diethylamine, triethylamine, monoisopropylamine, diisopropylamine, triisopropylamine, n-butylamine, monoethanolamine, diethanolamine, triethanolamine, monoisopropanolamine, diisopropanolamine, ethyleneimine, ethylenediamine, pyridine, tetramethylammonium hydroxide and mixture thereof.

9. (Original) The developer for a photopolymerizable presensitized plate for use in making a lithographic printing plate of claim 1, wherein it comprises a chelating agent for divalent metals.

10. (Original) The developer for a photopolymerizable presensitized plate for use in making a lithographic printing plate of claim 1, which has a conductivity ranging from 3 to 30 mS/cm.

Claims 11.-26. (Canceled)



## UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE  
 United States Patent and Trademark Office  
 Address: COMMISSIONER FOR PATENTS  
 P.O. Box 1450  
 Alexandria, Virginia 22313-1450  
 www.uspto.gov

## \*BIBDATASHEET\*

CONFIRMATION NO. 4993

Bib Data Sheet

SERIAL NUMBER 10/622,493	FILING DATE 07/21/2003  RULE	CLASS 430	GROUP ART UNIT 1752	ATTORNEY DOCKET NO. 018995-735
-----------------------------	---------------------------------------	--------------	------------------------	--------------------------------------

APPLICANTS

Hiroyuki Nagase, Shizuoka-Ken, JAPAN;  
 Kazuto Kunita, Shizuoka-Ken, JAPAN;

\*\* CONTINUING DATA \*\*\*\*\* *le*  
 This application is a DIV of 10/187,605 07/03/2002 PAT 6,641,980

\*\* FOREIGN APPLICATIONS \*\*\*\*\* *le*  
 JAPAN 2001-203609 07/04/2001

IF REQUIRED, FOREIGN FILING LICENSE GRANTED  
 \*\* 04/19/2004

Foreign Priority claimed 35 USC 119 (a-d) conditions met	<input checked="" type="checkbox"/> yes <input type="checkbox"/> no <input checked="" type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> Met after Allowance	STATE OR COUNTRY JAPAN	SHEETS DRAWING 4	TOTAL CLAIMS 10	INDEPENDENT CLAIMS 1
Verified and Acknowledged	<i>Heber Stan le</i> Examiner's Signature Initials				

ADDRESS  
 BURNS, DOANE, SWECKER & MATHIS, L.L.P.  
 P.O. Box 1404  
 Alexandria, VA  
 22313-1404

TITLE  
 Developer for photopolymerizable presensitized plate for use in making lithographic printing plate

FILING FEE  RECEIVED	FEES: Authority has been given in Paper No. _____ to charge/credit DEPOSIT ACCOUNT No. _____ for following:	<input type="checkbox"/> All Fees
		<input type="checkbox"/> 1.16 Fees ( Filing )
		<input type="checkbox"/> 1.17 Fees ( Processing Ext. of time )
		<input type="checkbox"/> 1.18 Fees ( Issue )



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FILE 'HCAPLUS' ENTERED AT 10:36:36 ON 22 FEB 2005

E NAGASE ?/AU

E E13-

E NAGASE H/AU

E NAGASE HIROYUKI/AU

L1 91 SEA ABB=ON PLU=ON "NAGASE HIROYUKI"/AU

E KUNITA KAZUTO/AU

L2 114 SEA ABB=ON PLU=ON "KUNITA KAZUTO"/AU

L3 6 SEA ABB=ON PLU=ON L1 AND L2

L4 0 SEA ABB=ON PLU=ON L3 AND LITHIGRAP?

L5 6 SEA ABB=ON PLU=ON L3 AND LITHOGRAP?

L6 4 SEA ABB=ON PLU=ON L5 AND PHOTOPOLYMER?

D SCAN

L7 1 SEA ABB=ON PLU=ON L6 AND ALKALI(A) SILICATE

D SCAN

SEL L7 RN

FILE 'REGISTRY' ENTERED AT 10:43:17 ON 22 FEB 2005

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107-15-3/BI OR 108-18-9/BI OR 109-73-9/BI OR 109-89-7/B  
I OR 110-86-1/BI OR 110-97-4/BI OR 111-42-2/BI OR  
11128-98-6/BI OR 121-44-8/BI OR 124-40-3/BI OR  
12794-95-5/BI OR 1310-58-3/BI OR 1310-65-2/BI OR  
1310-73-2/BI OR 1312-76-1/BI OR 1330-43-4/BI OR  
1332-77-0/BI OR 1344-09-8/BI OR 141-43-5/BI OR  
144-55-8/BI OR 151-56-4/BI OR 182005-17-0/BI OR  
26403-74-7/BI OR 26468-79-1/BI OR 298-14-6/BI OR  
3424-21-3/BI OR 385843-60-7/BI OR 385843-61-8/BI OR  
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56221-71-7/BI OR 584-08-7/BI OR 64-02-8/BI OR 65697-21-  
4/BI OR 68-04-2/BI OR 69778-08-1/BI OR 74-89-5/BI OR  
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OR 7558-79-4/BI OR 7601-54-9/BI OR 77-92-9/BI OR  
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78-96-6/BI OR 866-83-1/BI OR 9010-92-8/BI OR 98-73-7/BI  
)

D SCAN

FILE 'HCAPLUS' ENTERED AT 10:56:17 ON 22 FEB 2005  
D L7 ABS

FILE 'LREGISTRY' ENTERED AT 11:24:11 ON 22 FEB 2005

L9 STR  
L10 STR  
L11 STR  
L12 STR

FILE 'REGISTRY' ENTERED AT 11:27:54 ON 22 FEB 2005

L13 SCR 2043  
L14 50 SEA SSS SAM (L9 OR L10) AND (L11 OR L12) AND L13  
L15 255344 SEA SSS FUL (L9 OR L10) AND (L11 OR L12) AND L13  
L16 74546 SEA ABB=ON PLU=ON L15 AND 1-2/NC  
D QUE STAT L16  
D QUE STAT L15  
L17 STR  
L18 50 SEA SUB=L16 SSS SAM L17  
L19 64759 SEA SUB=L16 SSS FUL L17

FILE 'HCAPLUS' ENTERED AT 11:56:11 ON 22 FEB 2005

L20 202256 SEA ABB=ON PLU=ON L19  
L21 3979 SEA ABB=ON PLU=ON L20(L) (PHOTOSENS? OR LIGHTSENS? OR  
SENSIT?)  
L22 1421 SEA ABB=ON PLU=ON L21(L) TEM/RL  
L23 78 SEA ABB=ON PLU=ON L22 AND LITHOGRAPH? (2A) PRINT?  
L24 42 SEA ABB=ON PLU=ON L22(L) LITHOGRAPH? (2A) PRINT?  
L25 273 SEA ABB=ON PLU=ON L20(L) LITHOG? (A) PRINT?  
L26 1 SEA ABB=ON PLU=ON L25 AND L7  
L27 17 SEA ABB=ON PLU=ON L25 AND (LIGHT OR PHOTO) (A) SENSIT?  
L28 24 SEA ABB=ON PLU=ON L24 AND DEVELOP?  
L29 16 SEA ABB=ON PLU=ON L24 AND (SOLUTION? OR SOLN# OR  
SOLVENT?)  
L30 26 SEA ABB=ON PLU=ON L28 OR L29  
L31 40 SEA ABB=ON PLU=ON L30 OR L27 OR L26  
L32 3258 SEA ABB=ON PLU=ON L20(L) DEVELOP?  
L33 2205 SEA ABB=ON PLU=ON L32 AND PHOTO?/SC  
L34 56 SEA ABB=ON PLU=ON L33 AND (LIGHT OR PHOTO) (A) SENSIT?  
L35 26 SEA ABB=ON PLU=ON L34 AND (SOLUTION? OR SOLN# OR  
SOLVENT?)  
L36 25 SEA ABB=ON PLU=ON L35 NOT L31  
L37 8 SEA ABB=ON PLU=ON L36 AND TEM/RL  
L38 48 SEA ABB=ON PLU=ON L37 OR L31  
L39 24 SEA ABB=ON PLU=ON L38 AND (ALKALI OR SODIUM OR  
POTASSIUM OR LITHIUM OR AMMONIUM(A) SILICATE)  
D QUE L39  
L40 65 SEA ABB=ON PLU=ON L36 OR L31

L41 8 SEA ABB=ON PLU=ON L40 AND (ALKALI OR SODIUM OR  
 POTASSIUM OR LITHIUM OR AMMONIUM) (A) SILICATE  
 D FHITSTR  
 L42 1 SEA ABB=ON PLU=ON L41 AND L7

FILE 'REGISTRY' ENTERED AT 13:06:17 ON 22 FEB 2005  
 SAV TEMP L19 LE622/A

# FILE HCAPLUS

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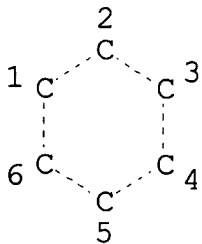
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LREGISTRY IS A STATIC LEARNING FILE

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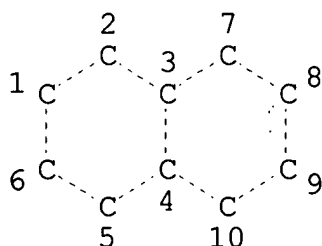
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 L2 114 SEA FILE=HCAPLUS ABB=ON PLU=ON "KUNITA KAZUTO"/AU  
 L3 6 SEA FILE=HCAPLUS ABB=ON PLU=ON L1 AND L2  
 L5 6 SEA FILE=HCAPLUS ABB=ON PLU=ON L3 AND LITHOGRAP?  
 L6 4 SEA FILE=HCAPLUS ABB=ON PLU=ON L5 AND PHOTOPOLYMER?  
 L7 1 SEA FILE=HCAPLUS ABB=ON PLU=ON L6 AND ALKALI (A) SILICA  
 TE  
 L9 STR



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DEFAULT MLEVEL IS ATOM  
DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:  
RSPEC I  
NUMBER OF NODES IS 6

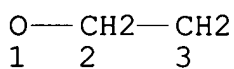
STEREO ATTRIBUTES: NONE  
L10 STR



NODE ATTRIBUTES:  
DEFAULT MLEVEL IS ATOM  
DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:  
RSPEC I  
NUMBER OF NODES IS 10

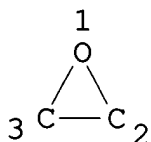
STEREO ATTRIBUTES: NONE  
L11 STR



NODE ATTRIBUTES:  
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DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:  
RING(S) ARE ISOLATED OR EMBEDDED  
NUMBER OF NODES IS 3

STEREO ATTRIBUTES: NONE  
L12 STR



## NODE ATTRIBUTES:

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

## GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

NUMBER OF NODES IS 3

## STEREO ATTRIBUTES: NONE

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AND L13

L16 74546 SEA FILE=REGISTRY ABB=ON PLU=ON L15 AND 1-2/NC

L17 STR

Cb 1

## NODE ATTRIBUTES:

CONNECT IS X2 RC AT 1

DEFAULT MLEVEL IS ATOM

GGCAT IS UNS AT 1

DEFAULT ECLEVEL IS LIMITED

ECOUNT IS M6-X10 C AT 1

## GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

NUMBER OF NODES IS 1

## STEREO ATTRIBUTES: NONE

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L20 202256 SEA FILE=HCAPLUS ABB=ON PLU=ON L19

L21 3979 SEA FILE=HCAPLUS ABB=ON PLU=ON L20 (L) (PHOTOSENS? OR  
LIGHTSENS? OR SENSIT?)

L22 1421 SEA FILE=HCAPLUS ABB=ON PLU=ON L21 (L) TEM/RL

L24 42 SEA FILE=HCAPLUS ABB=ON PLU=ON L22 (L) LITHOGRAPH? (2A) P  
RINT?

L25 273 SEA FILE=HCAPLUS ABB=ON PLU=ON L20 (L) LITHOG? (A) PRINT?

L26 1 SEA FILE=HCAPLUS ABB=ON PLU=ON L25 AND L7

L27 17 SEA FILE=HCAPLUS ABB=ON PLU=ON L25 AND (LIGHT OR  
PHOTO) (A) SENSIT?

L28 24 SEA FILE=HCAPLUS ABB=ON PLU=ON L24 AND DEVELOP?

L29 16 SEA FILE=HCAPLUS ABB=ON PLU=ON L24 AND (SOLUTION? OR  
SOLN# OR SOLVENT?)

L30 26 SEA FILE=HCAPLUS ABB=ON PLU=ON L28 OR L29

L31 40 SEA FILE=HCAPLUS ABB=ON PLU=ON L30 OR L27 OR L26

L32 3258 SEA FILE=HCAPLUS ABB=ON PLU=ON L20 (L) DEVELOP?

L33 2205 SEA FILE=HCAPLUS ABB=ON PLU=ON L32 AND PHOTO?/SC  
 L34 56 SEA FILE=HCAPLUS ABB=ON PLU=ON L33 AND (LIGHT OR  
 PHOTO) (A) SENSIT?  
 L35 26 SEA FILE=HCAPLUS ABB=ON PLU=ON L34 AND (SOLUTION? OR  
 SOLN# OR SOLVENT?)  
 L36 25 SEA FILE=HCAPLUS ABB=ON PLU=ON L35 NOT L31  
 L40 65 SEA FILE=HCAPLUS ABB=ON PLU=ON L36 OR L31  
 L41 8 SEA FILE=HCAPLUS ABB=ON PLU=ON L40 AND (ALKALI OR  
 SODIUM OR POTASSIUM OR LITHIUM OR AMMONIUM) (A) SILICATE

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L41 ANSWER 1 OF 8 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2004:963462 HCAPLUS

DOCUMENT NUMBER: 141:417961

TITLE: Alkaline **developing** liquid for  
 photosensitive lithographic printing plate

INVENTOR(S): Konuma, Taro; Suzuki, Toshitsugu

PATENT ASSIGNEE(S): Konica Minolta Medical & Graphic, Inc., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 34 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	
JP 2004317835	A2	20041111	JP 2003-112589	

2003

0417

PRIORITY APPLN. INFO.:

JP 2003-112589

2003

0417

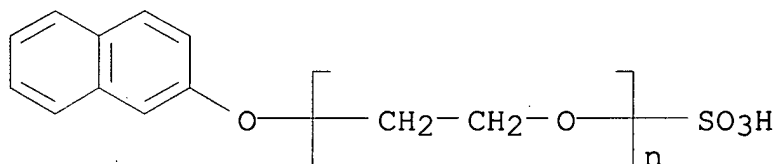
AB Title liquid comprises an alkaline substance and water-soluble surfactant

and is used to **develop** the formed image after laser

exposure on a lithog. printing plate which has a photosensitive

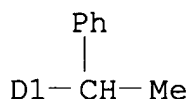
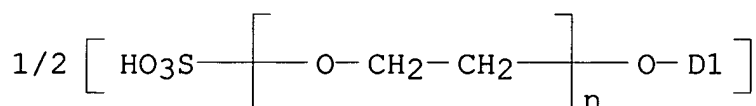
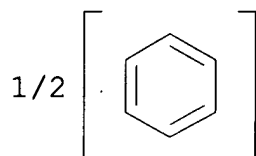
IT 81503-86-8 82009-26-5  
(alkaline **developing** liquid for **photosensitive**  
**lithog. printing** plate)

CN Poly(oxy-1,2-ethanediyl),  $\alpha$ -sulfo- $\omega$ -(2-naphthalenyloxy)-, sodium salt (9CI) (CA INDEX NAME)



● Na

CN Poly(oxy-1,2-ethanediyl),  $\alpha$ -sulfo- $\omega$ -[bis(1-phenylethyl)phenoxy]-, sodium salt (9CI) (CA INDEX NAME)



● Na

- IC ICM G03F007-32  
ICS G03F007-00
- CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
- ST alk **developing** liq photosensitive lithog printing
- IT Photolithography  
Surfactants  
(alkaline **developing** liquid for photosensitive lithog. printing plate)
- IT Alcohols, uses  
(alkoxylated; alkaline **developing** liquid for photosensitive lithog. printing plate)
- IT Polyoxyalkylenes, uses  
(mono(alkyl group)-terminated; alkaline **developing** liquid for photosensitive lithog. printing plate)
- IT 1312-76-1, **Potassium silicate** 3546-96-1  
9002-92-0, Polyethylene glycol monododecyl ether 25638-17-9  
37251-67-5, Ethylene oxide-propylene oxide copolymer monodecyl ether 37311-01-6 64366-70-7 **81503-86-8**  
**82009-26-5** 102640-44-8  
(alkaline **developing** liquid for **photosensitive lithog. printing** plate)



DOCUMENT NUMBER: 141:322631  
 TITLE: Lithographic printing plate precursor  
 INVENTOR(S): Maemoto, Kazuo; Hotta, Hisashi  
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
 SOURCE: Eur. Pat. Appl., 82 pp.  
 CODEN: EPXXDW  
 DOCUMENT TYPE: Patent  
 LANGUAGE: English  
 FAMILY ACC. NUM. COUNT: 3  
 PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
EP 1464513	A1	20041006	EP 2004-11675	2002 0723
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, FI, CY, TR, BG, CZ, EE, SK				
JP 2003034090	A2	20030204	JP 2001-221802	2001 0723
JP 2003034091	A2	20030204	JP 2001-221803	2001 0723
JP 2003063165	A2	20030305	JP 2001-256331	2001 0827
EP 1279520	A2	20030129	EP 2002-16280	2002 0723
EP 1279520	A3	20030618		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK				
PRIORITY APPLN. INFO.:			JP 2001-221802	A 2001 0723
			JP 2001-221803	A 2001 0723
			JP 2001-256331	A 2001 0827
			EP 2002-16280	A3

2002

0723

AB The invention concerns a lithog. printing plate precursor which does not require **development** and comprises an aluminum substrate, an image-recording layer and a hydrophilic film, and optionally an overcoat layer. The aluminum substrate is electrochem. surface-roughened in aqueous HCl **solution** and is provided with a hydrophilic film having d. 1,000-3,200 kg/m<sup>3</sup> and/or porosity 20-70%. Alternatively, the Al substrate has a surface-roughened shape with small pits; the average opening size of the small pits is 0.01-3 m and the ratio of the average depth of the small pit to the average opening size is 0.1-0.5. The image-recording layer comprises  $\geq 2$  types of fine particles selected from heat-fusible fine particles, polymer fine particles with a heat-reactive functional group, and a microcapsule containing a heat-reactive compound;  $\geq 1$  of the fine particles combines by heat to form an image. Alternatively this layer contains self water-dispersible resin fine particles which combine by heat, and the layer is writable by IR laser exposure. When the overcoat layer comprising a water-soluble resin is present, the image recording layer does not contain a hydrophilic binder resin, but does contain a hydrophobic polymer heat-combinable fine particle, a light-to-heat converting agent and a water-insol. compound with fluidity at 50°. The overcoat layer may contain a hydrophobic polymer fine particles and/or microcapsules; it may also contain a light-to-heat converting agent and have an optical d. at the exposure wavelength that is lower than that of the image recording layer. Printing plates of the invention prevent ablation and have increased printing durability.

IT **25167-42-4P**, Glycidyl methacrylate-styrene copolymer (particles; **lithog. printing** plate precursor from roughened aluminum with heat-**sensitive** polymer particles and microcapsules in recording layer and overcoat)

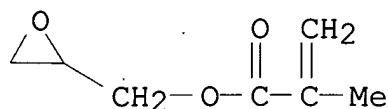
RN 25167-42-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, oxiranylmethyl ester, polymer with ethenylbenzene (9CI) (CA INDEX NAME)

CM 1

CRN 106-91-2

CMF C7 H10 O3



CM 2

CRN 100-42-5

CMF C8 H8

H<sub>2</sub>C=CH-Ph

IC ICM B41N003-03

ICS B41C001-10; C25F003-04

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 42

IT 1344-09-8, **Sodium silicate**

(aluminum hydrophilic treatment with; lithog. printing plate precursor from roughened aluminum with heat-sensitive polymer particles and microcapsules in recording layer and overcoat)

IT **25167-42-4P**, Glycidyl methacrylate-styrene copolymer(particles; **lithog. printing** plate precursor from roughened aluminum with heat-sensitive polymer particles and microcapsules in recording layer and overcoat)

L41 ANSWER 3 OF 8 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2004:779269 HCAPLUS

DOCUMENT NUMBER: 141:285849

TITLE: IR-sensitive direct-imaging lithographic printing plate precursors

INVENTOR(S): Nagashima, Akira

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 29 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2004264747

A2

20040924

JP 2003-57123

2003

0304

PRIORITY APPLN. INFO.:

JP 2003-57123

2003

0304

AB The title printing plate precursor has an olefinic resin, a novolak resin, and a light-to-heat converting compound on a hydrophilized support, wherein the olefinic resin is a copolymer of  $H_2C=C(-R_1)(-X-COOH)$  ( $R_1 = H$ , alkyl;  $X = \text{arylene}$ ,  $-CO-Y-$ ,  $-OCO-Y-$ ,  $-Ar-Y-$ ;  $Y = 2\text{-valent connecting group}$ ;  $Ar = \text{arylene}$ ) and (meth)acrylate, a (meth)acrylamide derivative, or a styrene derivative and

wherein the surface of the support is electrochem. roughened in acidic **solution** mainly containing hydrogen chloride. The printing plate precursor shows wide **development** latitude and provides printing plate of high printing durability.

IT 604813-66-3

(IR-sensitive direct-imaging lithog.  
printing plate precursors)

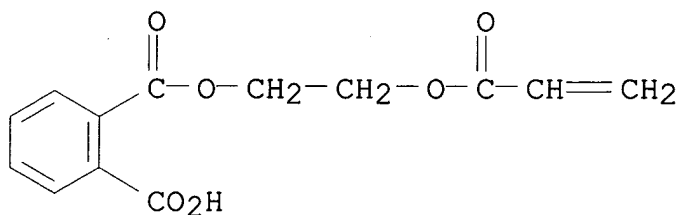
RN 604813-66-3 HCAPLUS

CN 1,2-Benzenedicarboxylic acid, mono[2-[(1-oxo-2-propenyl)oxy]ethyl] ester, polymer with butyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 30697-40-6

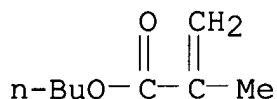
CMF C13 H12 O6



CM 2

CRN 97-88-1

CMF C8 H14 O2



IC ICM G03F007-033  
 ICS B41N001-08; B41N003-03; G03F007-004; G03F007-09  
 CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and  
 Other Reprographic Processes)  
 Section cross-reference(s): 35  
 IT 604813-23-2 604813-56-1 604813-57-2 604813-62-9  
 604813-64-1 604813-65-2 **604813-66-3** 760965-90-0  
 (IR-sensitive direct-imaging lithog.  
 printing plate precursors)  
 IT 1344-09-8, **Sodium silicate**  
 (hydrophilizing agent; IR-sensitive direct-imaging lithog.  
 printing plate precursors)

L41 ANSWER 4 OF 8 HCAPLUS COPYRIGHT 2005 ACS on STN  
 ACCESSION NUMBER: 2003:272184 HCAPLUS  
 DOCUMENT NUMBER: 138:294954  
 TITLE: Method for developing direct-imaging  
 positive-working lithographic printing plate  
 precursors with specific developer  
**solution**  
 INVENTOR(S): Serikawa, Takeshi  
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 21 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2003107742	A2	20030409	JP 2001-297245	

2001  
0927

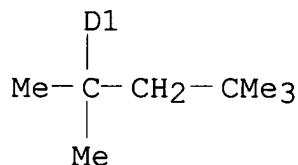
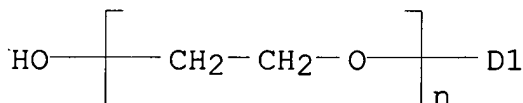
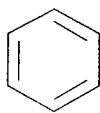
PRIORITY APPLN. INFO.: JP 2001-297245

2001  
0927

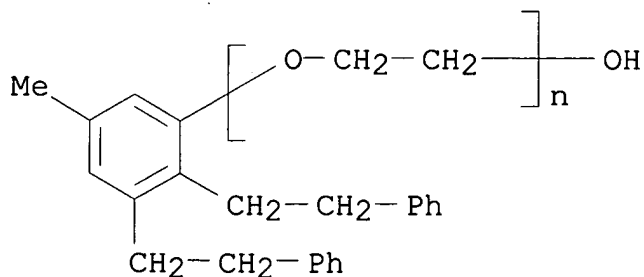
AB The title method for developing direct-imaging pos.-working  
 lithog. printing plate precursors having a **light-**  
**sensitive** layer, which contains a light-to-heat converting

compound and an alkali solubilizable resin with phenolic hydroxy groups, on a support, includes the steps of exposing the plate precursor with a laser beam and developing the plate precursor with a developer **solution**, wherein the developer **solution** has  $\geq 12$  pH and contains 10,000 ppm surfactant, an alkali metal hydroxide, and alkali metal silicate. The method provides high contrast images, thick image layers, wide development latitude, and developer of the long service-life.

IT **9036-19-5**, Noigen EA 120 **55901-03-6**, Newcol 723  
 (surfactant; **developer solution**)  
 RN 9036-19-5 HCAPLUS  
 CN Poly(oxy-1,2-ethanediyl),  $\alpha$ -[(1,1,3,3-tetramethylbutyl)phenyl]- $\omega$ -hydroxy- (9CI) (CA INDEX NAME)



RN 55901-03-6 HCAPLUS  
 CN Poly(oxy-1,2-ethanediyl),  $\alpha$ -[5-methyl-2,3-bis(2-phenylethyl)phenyl]- $\omega$ -hydroxy- (9CI) (CA INDEX NAME)



IC ICM G03F007-32  
 ICS G03F007-00; G03F007-004  
 CC 74-6 (Radiation Chemistry, **Photochemistry**, and  
**Photographic** and Other Reprographic Processes)  
 IT Lithographic plates  
 (method for developing direct-imaging pos.-working lithog.  
 printing plate precursors with specific developer **soln**  
 .)  
 IT Surfactants  
 (nonionic, Pluronic TR 702; developer **solution**)  
 IT Polyoxyalkylenes, processes  
 (surfactant; developer **solution**)  
 IT 1312-76-1, **Potassium silicate**  
 (developer **solution**)  
 IT 1310-58-3, Potassium hydroxide, processes  
 (developer **solution**; developer **solution**)  
 IT 139-07-1, Texnol R 5 1652-63-7, Fluorad FC 135 **9036-19-5**  
 , Noigen EA 120 11140-78-6, Amogen "K" 25322-68-3, PEG 200  
**55901-03-6**, Newcol 723 82030-82-8, Surflon S 121  
 106392-12-5, Pluronic P 84  
 (surfactant; **developer solution**)

L41 ANSWER 5 OF 8 HCAPLUS COPYRIGHT 2005 ACS on STN  
 ACCESSION NUMBER: 2003:272163 HCAPLUS  
 DOCUMENT NUMBER: 138:294951  
 TITLE: Preparation of photosensitive lithographic  
 printing plate  
 INVENTOR(S): Hino, Etsuko; Kasakura, Akio; Ogita, Naohide  
 PATENT ASSIGNEE(S): Mitsubishi Chemical Corp., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 10 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2003107683	A2	20030409	JP 2001-302202	2001 0928

PRIORITY APPLN. INFO.: JP 2001-302202  
 2001  
 0928

AB A lithog. printing plate comprises, on the surface of a substrate,  
 a pos.-working photosensitive layer, consisting of an alkali-soluble

resin and a photothermal converting substance which absorbs light from an image exposure light source and converts to heat. The preparation process comprises scanning exposure to a laser light source

and **developing** with a **developing soln**

. containing alkali in certain concentration (A weight%) and a surfactant in

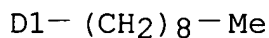
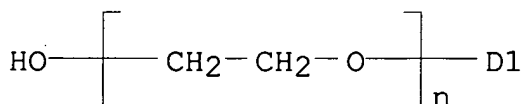
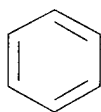
certain concentration (S weight%) using an automatic **developing** device and is characterized in that the **development** is carried out while replenishing with a replenishment **developing solution** (a) having an alkali concentration higher than A weight% and a replenishment **developing** liquid (b) having a surfactant concentration higher than S weight%.

IT 9016-45-9, Nikkol NP 15

(preparation of **photosensitive lithog. printing plate**)

RN 9016-45-9 HCAPLUS

CN Poly(oxy-1,2-ethanediyl),  $\alpha$ -(nonylphenyl)- $\omega$ -hydroxy-  
(9CI) (CA INDEX NAME)



IC ICM G03F007-00

ICS G03F007-004; G03F007-32

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST photosensitive lithog printing plate **developing soln**

IT 1310-58-3, Potassium hydroxide, uses 1312-76-1,  
**Potassium silicate**

(alkali concentration of **developing soln**

.; preparation of photosensitive lithog. printing plate)

IT 9016-45-9, Nikkol NP 15

(preparation of **photosensitive lithog. printing plate**)



IT 11140-78-6 42612-52-2, Nikkol DLP10 156510-75-7, Pionin A 15  
 (surfactant concentration of **developing solution**;  
 preparation of photosensitive lithog. printing plate)

L41 ANSWER 6 OF 8 HCAPLUS COPYRIGHT 2005 ACS on STN  
 ACCESSION NUMBER: 2003:173064 HCAPLUS  
 DOCUMENT NUMBER: 138:212836  
 TITLE: Method for preparing lithographic printing  
 plate  
 INVENTOR(S): Nagase, Hiroyuki  
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
 SOURCE: Eur. Pat. Appl., 57 pp.  
 CODEN: EPXXDW  
 DOCUMENT TYPE: Patent  
 LANGUAGE: English  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
EP 1288722	A2	20030305	EP 2002-18272	2002 0822
EP 1288722	A3	20031015		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK				
JP 2003066621	A2	20030305	JP 2001-254289	2001 0824
JP 2003066622	A2	20030305	JP 2001-254290	2001 0824
JP 2003066623	A2	20030305	JP 2001-254291	2001 0824
JP 2003066624	A2	20030305	JP 2001-254292	2001 0824
US 2003138732	A1	20030724	US 2002-222903	2002 0819
US 6756183	B2	20040629		
PRIORITY APPLN. INFO.:			JP 2001-254289	A 2001 0824

JP 2001-254290 A 2001  
0824

JP 2001-254291 A 2001  
0824

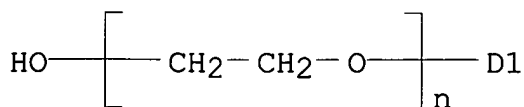
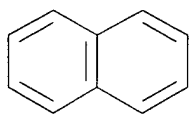
JP 2001-254292 A 2001  
0824

AB A method for preparing a lithog. printing plate comprises the steps of imagewise exposing, to light, a presensitized plate for use in making a lithog. printing plate, which comprises a grained and anodized substrate provided on it with a photopolymerizable **light-sensitive** layer containing a compound having at least one addition-polymerizable ethylenically unsatd. double bond and a titanocene type initiator; and then developing the light-exposed presensitized plate using a developer which comprises a surfactant and a weak acid or a salt of it having a dissociation constant pKa ranging 10-13, and has a pH value ranging 11.5-12.8. The method exhibits excellent development performance, and gives good results to the resultant printing plate in terms of printing durability and scumming. In addition, the change in pH value of the developer is so small that the stable development can be ensured for a long period of time.

IT **69778-08-1**  
(nonionic surfactant; developer of preparing **lithog.**  
**printing** plate containing)

RN 69778-08-1 HCAPLUS

CN Poly(oxy-1,2-ethanediyl),  $\alpha$ -naphthalenyl- $\omega$ -hydroxy-  
(9CI) (CA INDEX NAME)



IC ICM G03F007-32

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and

Other Reprographic Processes)

Section cross-reference(s): 35, 38

IT Lithographic plates

(preparing lithog. printing plate containing photopolymerizable  
**light-sensitive** layer)

IT 57-50-1, Saccharose, uses 58-63-9, Inosine 97-05-2,  
Sulfosalicylic acid 98-73-7, p-tert-Butyl benzoic acid  
102-71-6, uses 111-42-2, uses 127-06-0, Acetoxime 147-93-3,  
Thiosalicylic acid 1312-76-1, **Potassium**  
**silicate** 3088-27-5 7664-38-2, Phosphoric acid, uses  
7757-83-7, Sodium sulfite 10117-38-1, Potassium sulfite  
62546-15-0 106392-12-5, Pluronic P84 125605-97-2

(developer of preparing lithog. printing plate containing)

IT **69778-08-1** 87068-17-5, Pelex NBL

(nonionic surfactant; developer of preparing **lithog.**  
**printing** plate containing)

IT 113506-31-3P 182005-17-0P 385843-60-7P 385843-61-8P  
483303-17-9P 483303-19-1P

(preparing lithog. printing plate containing photopolymerizable  
**light-sensitive** layer)

L41 ANSWER 7 OF 8 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2003:113125 HCAPLUS

DOCUMENT NUMBER: 138:161108

TITLE: Method for lithographic plate making using  
printing plate precursors with specific  
intermediate layer and specific developing  
**solution**

INVENTOR(S): Kondo, Shunichi

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 25 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2003043693	A2	20030213	JP 2001-235810	

2001  
0803

PRIORITY APPLN. INFO.:

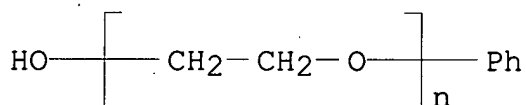
JP 2001-235810

2001  
0803

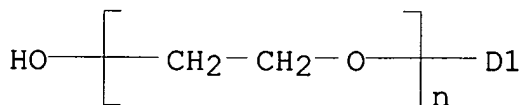
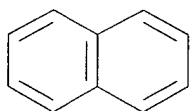
AB The title method uses a lithog. printing plate precursor having an

intermediate layer and a **light-sensitive** layer made of photopolymerizable materials and a developing **soln** ., wherein the intermediate layer contains a polymer having phosphoric acid groups in the side chain and wherein the developing **solution** contains an inorg. alkali salt and a nonionic surfactant having polyoxyalkylene ether and has 11.0-12.7 pH. The method provides the printing plate showing the good storageability.

- IT **9004-78-8**, Polyoxyethylene phenyl ether **69778-08-1**  
 (developing solution; method for lithog. plate making using printing plate precursors)  
 RN 9004-78-8 HCAPLUS  
 CN Poly(oxy-1,2-ethanediyl),  $\alpha$ -phenyl- $\omega$ -hydroxy- (9CI)  
 (CA INDEX NAME)



- RN 69778-08-1 HCAPLUS  
 CN Poly(oxy-1,2-ethanediyl),  $\alpha$ -naphthalenyl- $\omega$ -hydroxy- (9CI) (CA INDEX NAME)



- IC ICM G03F007-11  
 ICS G03F007-00; G03F007-32  
 CC 74-6 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)  
 Section cross-reference(s): 35  
 ST lithog plate precursor intermediate layer developing **soln**  
 IT 1310-58-3, Potassium hydroxide, uses 1312-76-1,  
**Potassium silicate 9004-78-8**,  
 Polyoxyethylene phenyl ether **69778-08-1**  
 (developing solution; method for lithog. plate making using printing plate precursors)

L41 ANSWER 8 OF 8 HCAPLUS COPYRIGHT 2005 ACS on STN  
 ACCESSION NUMBER: 2003:20988 HCAPLUS  
 DOCUMENT NUMBER: 138:98218  
 TITLE: Developer for **photopolymerizable**  
 presensitized plate for use in making  
**lithographic** printing plate and method  
 for preparing **lithographic** printing  
 plate  
 INVENTOR(S): **Nagase, Hiroyuki; Kunita,**  
**Kazuto**  
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
 SOURCE: Eur. Pat. Appl., 51 pp.  
 CODEN: EPXXDW  
 DOCUMENT TYPE: Patent  
 LANGUAGE: English  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
EP 1273972	A1	20030108	EP 2002-14848	2002 0703
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK				
JP 2003015318	A2	20030117	JP 2001-203609	2001 0704
US 2003118951	A1	20030626	US 2002-187605	2002 0703
US 6641980	B2	20031104		
PRIORITY APPLN. INFO.:			JP 2001-203609	A 2001 0704

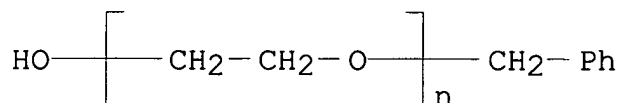
AB A developer for a **photopolymerizable** presensitized plate  
 for use in making a **lithog.** printing plate characterized  
 comprises an **alkali silicate** and a nonionic  
 compound represented by A-W (A = hydrophobic organic group whose logP  
 as determined for A-H is not less than 1.5; W = nonionic hydrophilic  
 organic group whose logP as determined for W-H is less than 1.0), it  
 has a  
 molar ratio: SiO<sub>2</sub>/M<sub>2</sub>O (M = alkali metal or an ammonium group)  
 ranging from 0.75-4.0, a pH value ranging from 11.5-12.8 and a

conductivity ranging from 3-30 mS/cm. A method for preparing a **lithog.** printing plate comprises the steps of imagewise exposing, to light, a presensitized plate for use in making a **lithog.** printing plate, which comprises a substrate provided on it with a **photopolymerizable light-sensitive** layer containing a compound having at least one addition-polymerizable ethylenically unsatd. double bond and a **photopolymn.** initiator; and then developing the exposed presensitized plate using the above developer. The developers and the method for making a **lithog.** printing plate according to the present invention can prevent scumming during printing and simultaneously attain sufficient printing durability without impairment of image-forming performance, and the developer can dissolve or disperse stably for a long period of time the compds. which are not soluble in the developer, and therefore the running performance of the developer can be excellent and stabilized.

IT **26403-74-7 26468-79-1 69778-08-1**  
**386214-35-3 386214-38-6 386214-40-0**  
 (surfactant; developer for **photopolymerizable**  
 presensitized plate for use in making **lithog.**  
**printing** plate containing)

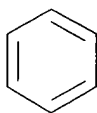
RN 26403-74-7 HCAPLUS

CN Poly(oxy-1,2-ethanediyl),  $\alpha$ -(phenylmethyl)- $\omega$ -hydroxy-  
 (9CI) (CA INDEX NAME)

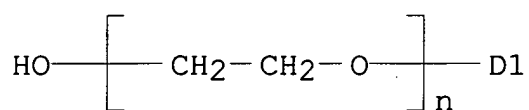


RN 26468-79-1 HCAPLUS

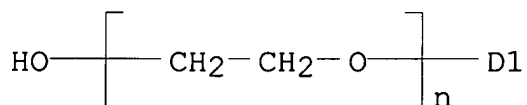
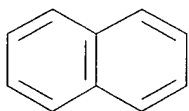
CN Poly(oxy-1,2-ethanediyl),  $\alpha$ -[(1,1-dimethylethyl)phenyl]-  
 $\omega$ -hydroxy- (9CI) (CA INDEX NAME)



D1-Bu-t

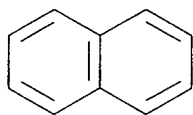


RN 69778-08-1 HCAPLUS

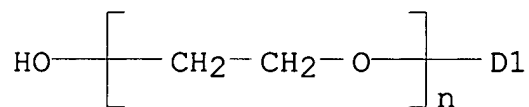
CN Poly(oxy-1,2-ethanediyl),  $\alpha$ -naphthalenyl- $\omega$ -hydroxy-  
(9CI) (CA INDEX NAME)

RN 386214-35-3 HCAPLUS

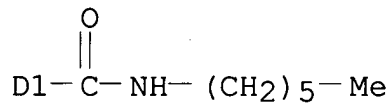
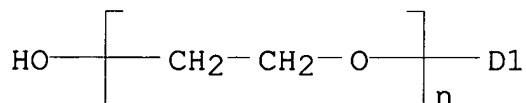
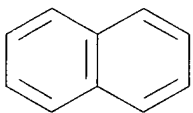
CN Poly(oxy-1,2-ethanediyl),  $\alpha$ -[(1,1-dimethylethyl)naphthalenyl]- $\omega$ -hydroxy- (9CI) (CA INDEX NAME)



D1-Bu-t



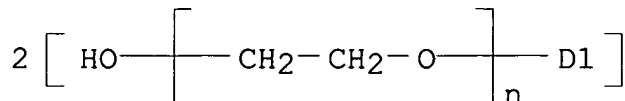
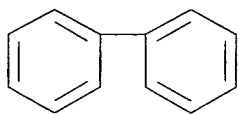
RN 386214-38-6 HCAPLUS

CN Poly(oxy-1,2-ethanediyl),  $\alpha$ -[[ (hexylamino) carbonyl] naphthalenyl]- $\omega$ -hydroxy- (9CI) (CA INDEX NAME)

RN 386214-40-0 HCAPLUS

CN Poly(oxy-1,2-ethanediyl),  $\alpha,\alpha'$ -[1,1'-biphenyl]-ar,ar'-diylbis[ $\omega$ -hydroxy- (9CI) (CA INDEX NAME)]





- IC ICM G03F007-32  
ICS G03F007-027
- CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)  
Section cross-reference(s): 35, 38
- ST developer **photopolymerizable** presensitized plate  
**lithog** printing
- IT **Lithographic** plates  
(developer for **photopolymerizable** presensitized plate for use in making **lithog.** printing plate)
- IT Polymerization  
(**photopolymn.**; developer for **photopolymerizable** presensitized plate for use in making **lithog.** printing plate)
- IT 98-73-7 9010-92-8, Styrene-methacrylic acid copolymer 65697-21-4  
(additive; developer for **photopolymerizable** presensitized plate for use in making **lithog.** printing plate containing)
- IT 64-02-8, Tetrasodium ethylenediaminetetraacetate 77-92-9, Citric acid, uses 56221-71-7  
(chelating agent; developer for **photopolymerizable** presensitized plate for use in making **lithog.** printing plate containing)
- IT 68-04-2, Sodium citrate 74-89-5, Monomethylamine, uses 75-04-7, Monoethylamine, uses 75-31-0, Monoisopropylamine, uses 75-50-3, Trimeth-ylamine, uses 75-59-2, Tetramethylammonium hydroxide 78-96-6, Monoisopropanolamine 102-71-6, Triethanolamine, uses 107-15-3, Ethylenediamine, uses 108-18-9, Diisopropylamine 109-73-9, n-Butylamine, uses 109-89-7, Diethylamine, uses 110-86-1, Pyridine, uses 110-97-4, Diisopropanolamine 111-42-2, Diethanolamine, uses 121-44-8, Triethylamine, uses 124-40-3, Dimethylamine, uses 141-43-5, Monoethanolamine, uses 144-55-8, Sodium bicarbonate, uses 151-56-4, Ethyleneimine, uses 298-14-6, Potassium bicarbonate 497-19-8, Sodium carbonate, uses 506-87-6,

Am-monium carbonate 584-08-7, Potassium carbonate 866-83-1,  
Potassium citrate 1066-33-7, Ammonium bicarbonate 1310-58-3,  
Potassium hydroxide, uses 1310-65-2, Lithium hydroxide  
1310-73-2, Sodium hydroxide, uses 1312-76-1, **Potassium**  
**silicate** 1330-43-4, Sodium borate 1332-77-0,  
Potas-sium borate 1344-09-8, **Sodium silicate**  
3424-21-3, Triisopropylamine 7558-79-4 7601-54-9, Sodium  
tertiary phosphate 7722-76-1, Ammonium phosphate 7758-11-4  
7778-53-2 11128-98-6, Ammonium borate 12794-95-5,

**Ammonium silicate**

(developer for **photopolymerizable** presensitized plate  
for use in making **lithog.** printing plate containing)

IT 182005-17-0P 385843-60-7P 385843-61-8P 483303-16-8P  
483303-17-9P 483303-19-1P

(**photopolymerizable** presensitized plate for use in  
making **lithog.** printing plate)

IT **26403-74-7 26468-79-1 69778-08-1**  
386214-34-2 **386214-35-3 386214-38-6**  
**386214-40-0**

(surfactant; developer for **photopolymerizable**  
presensitized plate for use in making **lithog.**  
**printing** plate containing)

REFERENCE COUNT: 15 THERE ARE 15 CITED REFERENCES AVAILABLE  
FOR THIS RECORD. ALL CITATIONS AVAILABLE  
IN THE RE FORMAT